



SILICON OXIDE

Sputtering Target

Silicon dioxide, also known as silica, has a chemical formula of SiO2. Silicon(II) oxide sputtering target coatings are used for optical applications in reflectors, flood lamps, mirrors, jewelry, and other products. The coatings can reduce reflection in the near infrared range or act as interference layers. It is used in thin-film capacitors, hybrid circuits, semiconductor components and other electronic applications.

Quick Facts

Product Silicon Oxide Sputtering Target

Stock No NS6130-10-1057

CAS 7631-86-9

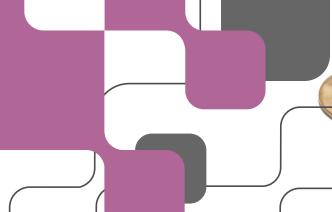
Backing Plate (As per Customer requirement)

Additional Characteristics

Stock No.	Purity	Diameter	Thickness
NS6130-10-1057	99.99%	50.8 mm ± 1mm	3 mm ± 0.5mm

Technical Specification

Molecular Formula	Molecular Weight	Melting Point
SiO ₂	60.08g/mol	1610°C

















ISO 9001:2015 CERTIFIED COMPANY **INTELLIGENT MATERIALS PVT LTD**

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